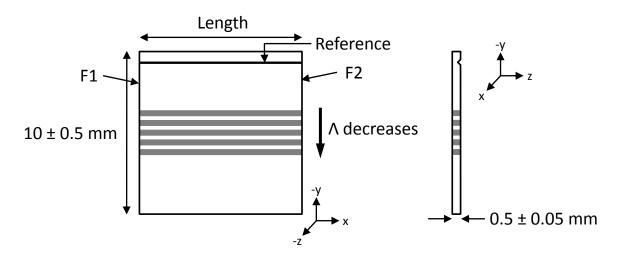
Device Specification MDFG2-0.5-xx



[Image for reference only. Not to scale.]

Description MgO doped PPLN DFG crystal for 1064nm and 775-869nm

Thickness(z) 0.5mm± 0.05mm

Width(y) 10mm±0.5mm

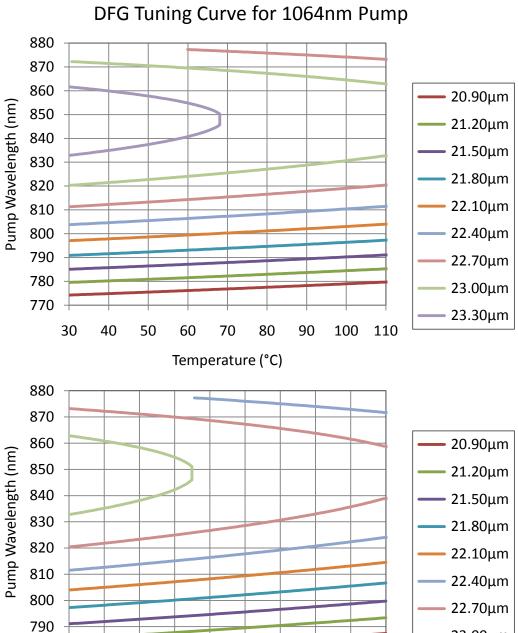
Length(x) 40mm±0.5mm or 20mm±0.5mm

 $Periods(\Lambda)$ 20.90, 21.20, 21.50, 21.80, 22.10, 22.40, 22.70, 23.00, 23.30µm

NOTES:

- 1 The DFG device material is Magnesium doped Lithium Niobate with nine periodically poled gratings. Each grating is 0.5mm wide with individual periods as listed above. A saw-cut reference mark is provided on the +z face of the crystal to determine the largest grating period (see above diagram). Each poled grating is separated by 0.2mm wide regions of unpoled material.
- 2 The average mark-to-space ratio of each grating is better than 70:30.
- 3 Each device is etched to make the poled gratings visible. Due to the wet-etch nature of this process the top and bottom surface finish of each device may appear cloudy or uneven.
- 4 Perpendicularity of input/output facets F1 and F2 to gratings is within ±0.15°. Parallelism between end facets F1 and F2 is within ±5 minutes.
- Optical finish of facets F1 and F2 is within 20/10 scratch dig with $\lambda/8@1064$ nm. No more than two 100 μ m size chips per end facet.
- AR coated to R<1.5% @ 700-1100nm for the input facet (F2) and 2.4-4.8 μ m for the output facet (F1).

Device Specification MDFG2-0.5-xx



110 120 130 140 150 160 170 180 190 200

780

23.00µm

23.30µm